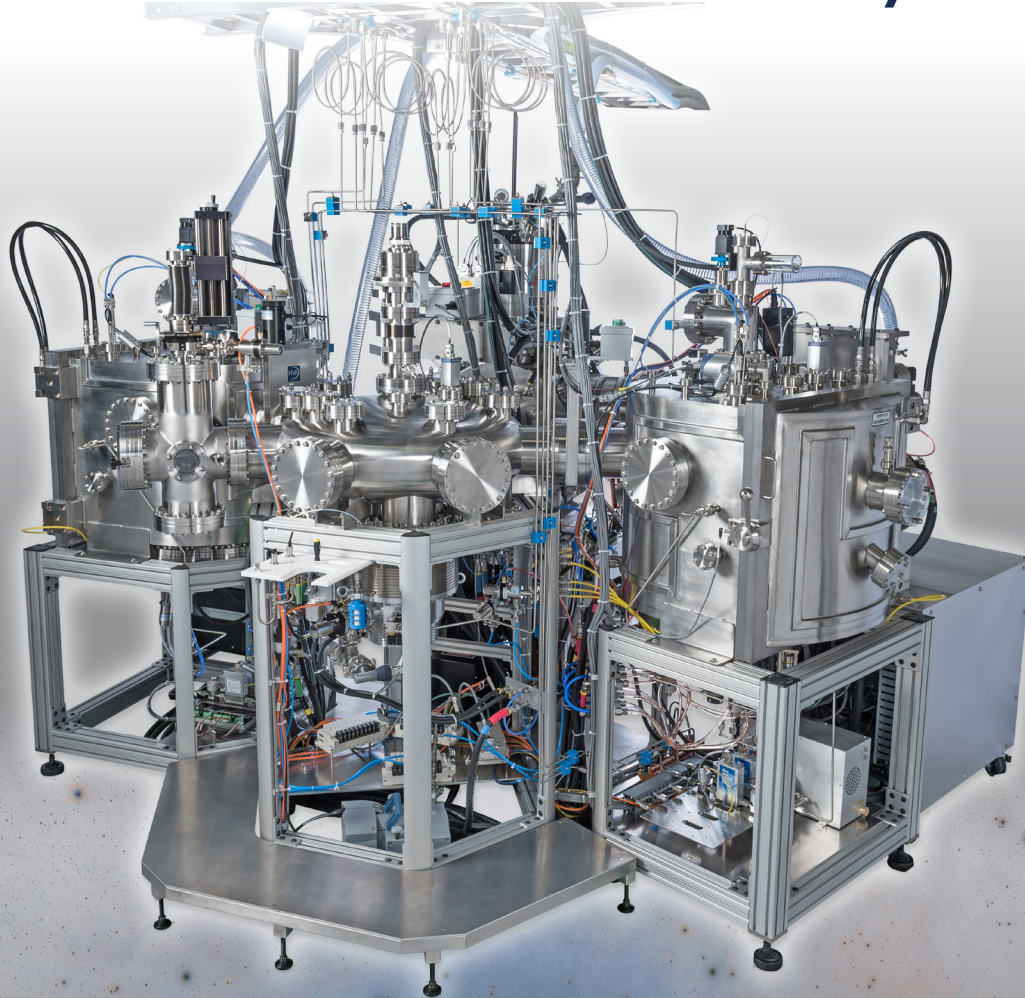


PLEIADES Cluster System

Customizable Multi-Chamber Array



Process Modules Available:

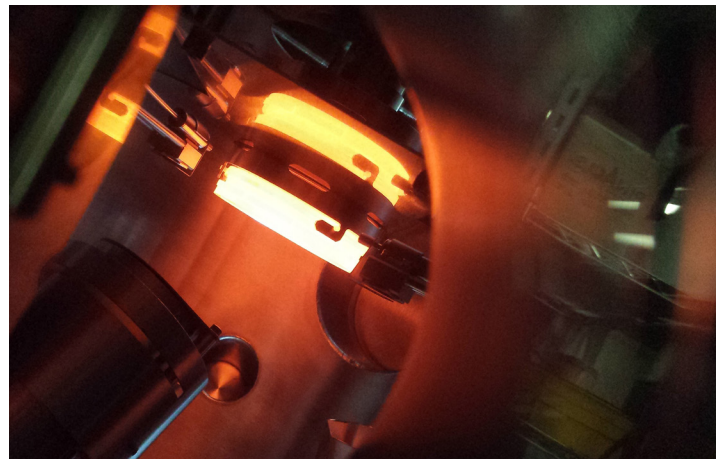
- Ion Beam Etching & Sputtering
- Atomic Layer Deposition
- Thermal Evaporation
- eBeam Evaporation - Lift Off
- Magnetron Sputtering Metals
- Oxide & Fluoride Evaporation
- Magnetron Sputtering Oxides & Nitrides

 **Intivac**
T H I N F I L M

PLEIADES CLUSTER THIN FILM PROCESSING SYSTEM

The Pleiades (Seven Sisters) System will accommodate your most demanding process requirements. This system allows you to maintain UHV conditions for transfer of your substrates to perform a wide range of thin film processes.

Pleiades can easily cool full wafers to -90°C , while others may be held at temperatures up to 1000°C using our new "Helios" substrate heater.



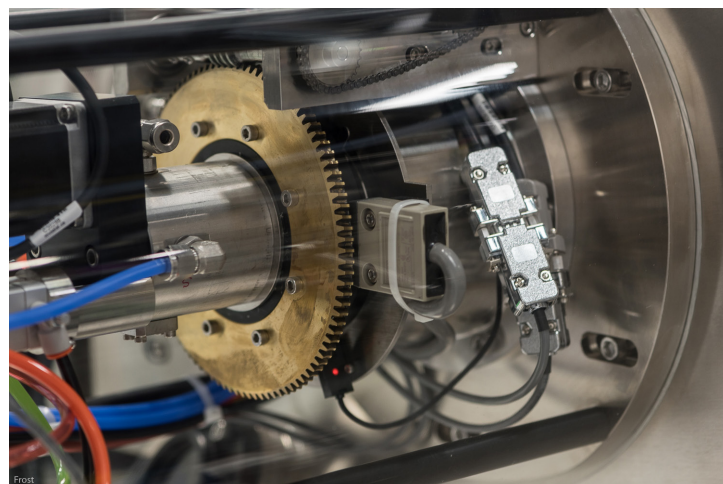
HEATING AND COOLING:

- Direct water-cooled stage with ability to etch at multiple angles in a single automated process etch
- LN2 cooled stage (down to $<- 100\text{K}$) with Incident Angle Tilt
- High temperature radiative SiC

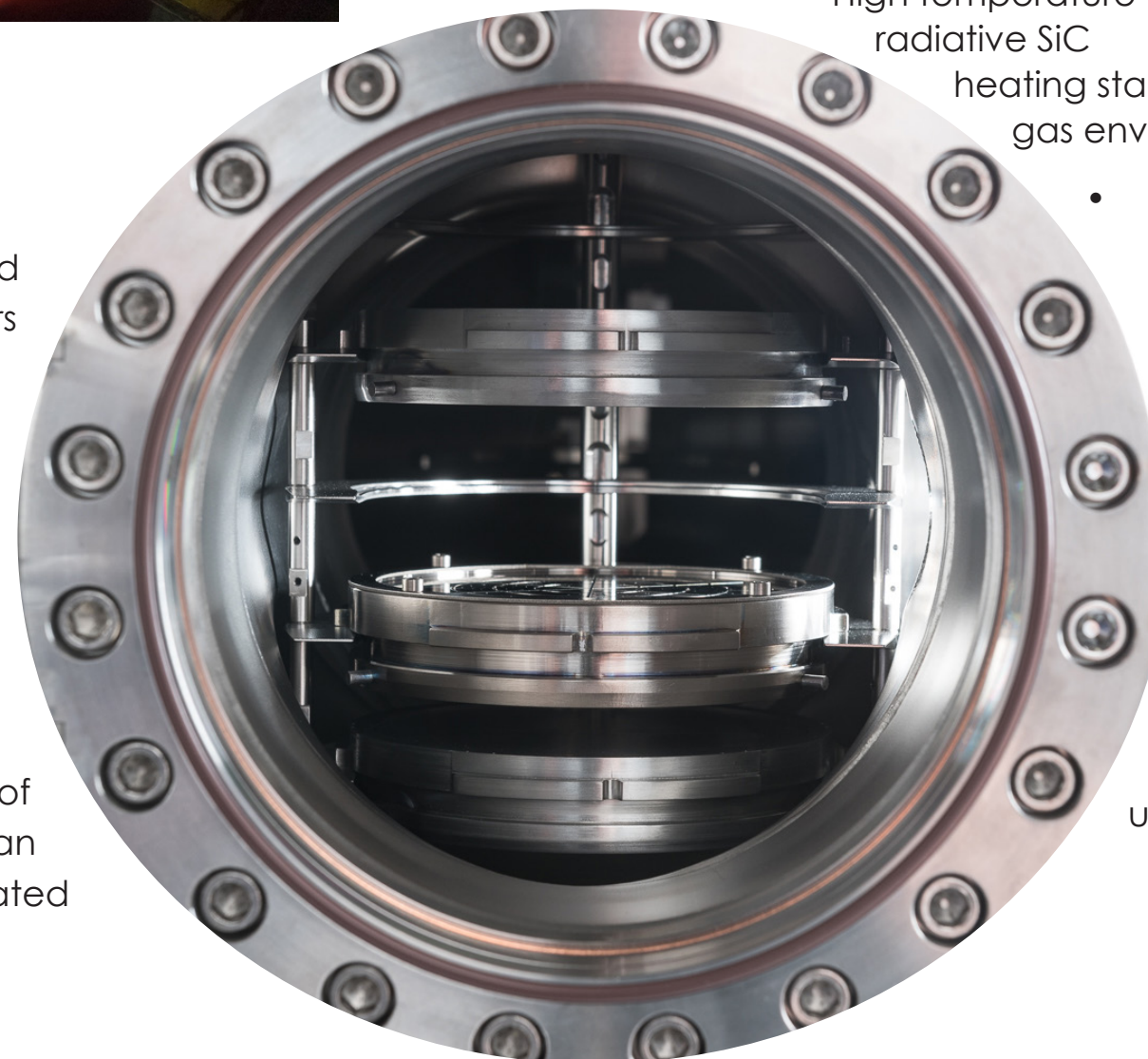


SYSTEM CAPABILITIES:

- State-of-the-art cluster system capable of producing and etching thin films of II-VI materials on up to 100mm wafers
- Central radial distribution chamber provides access to all satellite systems with telescopic transfer arm
- Load-lock chamber allows manual loading/unloading and storing of multiple sample carriers at one time



- Can be tailored to address corrosive and toxic properties of materials that can be accommodated in the machine



heating stage, designed for operation in corrosive gas environment

- High-efficiency heating with exquisite radiative heat management
- Maximum 1150°C operating temperature, measured behind the sample/wafer carrier
- The sample/wafer carriers can be blank or hollowed out in the center (with direct exposure of wafer to the heater element)
- Both the heated and the water-cooled stages provide continuous rotation for maximized temperature uniformity across the wafer

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SYSTEM ADVANTAGES:

- Versatile design incorporating automatic thin film evaporation, sputter deposition and sample preparation modules, suited for dealing with low melting points, high vapor pressures and corrosive properties of demanding source materials
- Each technique is performed in a separate process chamber with its own dedicated power supply, control system and computer
- Configurable and expandable system architecture to include up to seven independent systems and fully motorized transfer capability



PROVIDING LEADING-EDGE TECHNOLOGY SOLUTIONS

At Intlvac, we design and manufacture a wide variety of systems for Thin Film PVD and Etch. Our product line ranges from small R&D/pilot project systems to large production systems utilizing processes such as Ion Beam Etching, Sputtering, E-beam, Thermal Evaporation, Fiber-optic coating, and more! Call today to discuss your specific requirements.



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